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Substitute for form 1449/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)			Complete If Known		
			Application Number	10/597,199-Conf. #7625	
			Filing Date	July 14, 2006	
			First Named Inventor	Karsten Buse	
			Art Unit	NMA 1792	
			Examiner Name	Not Yet Assigned Hiteshew	
Sheet	1	of	1	Attorney Docket Number	20811/0204481-USO

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (If known)				
/F.H./	AA*	US-3,700,912		10-24-1972	Glass et al.	
/F.H./	AB*	US-3,932,299		01-13-1976	Phillips	
/F.H./	AC*	US-4,398,248		08-02-1983	Holman	
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Examiner Initials*	Cite No. ¹	Foreign Patent Document		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T
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/F.H./	BA	DE-10300080		07-22-2004	Deutsche Telekom Ag		✓

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NON PATENT LITERATURE DOCUMENTS						
Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				72
/F.H./	CA	A.A. BUKHARAEV et al.: "Investigation of iron impurity centres in lithium niobate", Fizika Tverdogo Tela, USSR, Feb. 1976, ISSN 0367-3294, Soviet Physics - Solid State, USA, ISSN 0038-5854, XP-002320127 (1 page).				
/F.H./	CB	K. BUSE et al.: "Development of thermally fixed holograms in photorefractive lithium-niobate crystals without light", Optical Materials 18 (2001), Elsevier Science B.V., pp. 17-18 (2 pages).				
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/F.H./	CE	L. GALAMBOS et al.: "Doubly doped stoichiometric and congruent lithium niobate for holographic data storage", Journal of Crystal Growth 229 (2001), Elsevier Science B.V., pp. 228-232 (5 pages).				
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/F.H./	CG	T. ZHANG et al.: "Optical damage resistance of In:Fe:LiNbO ₃ crystals related to the defect structure", Materials Letters 58 (2004), science direct, Elsevier B.V., pp. 3074-3078 (5 pages).				

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Examiner Signature	/Felisa Hiteshew/	Date Considered	01/18/2008
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